

FIG. 1

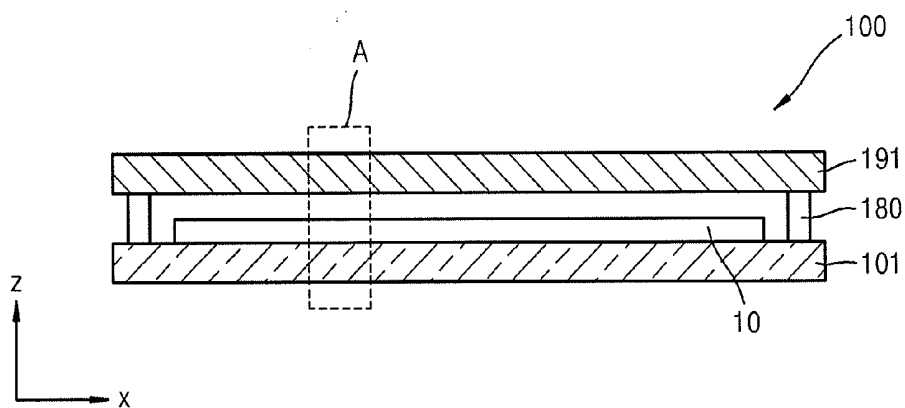


FIG. 2

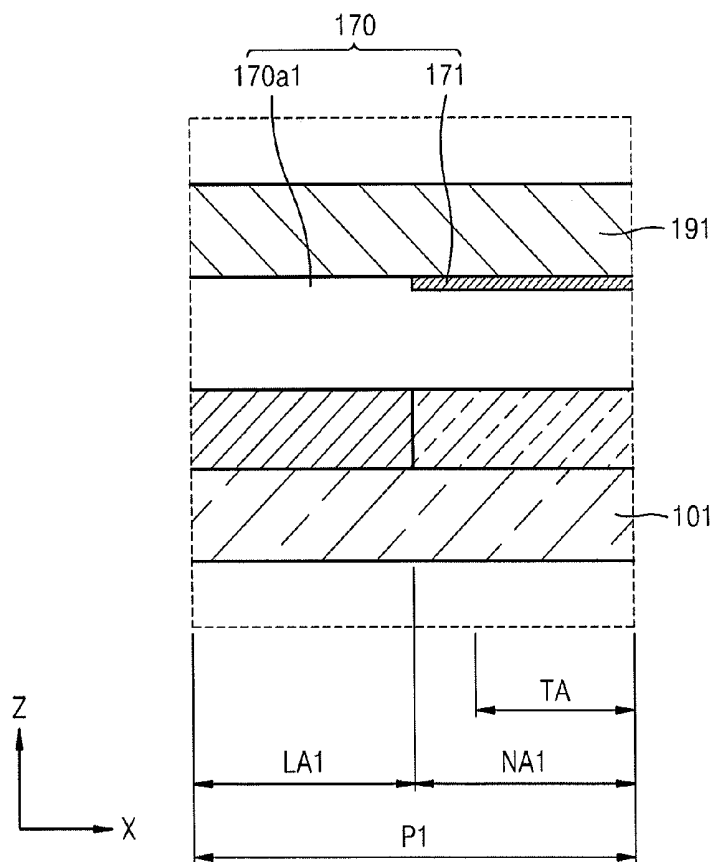


FIG. 3

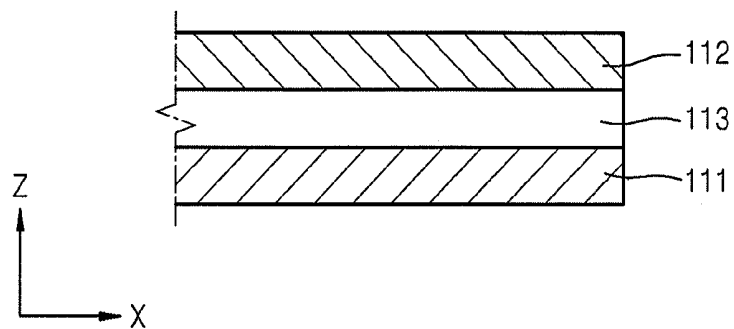


FIG. 4

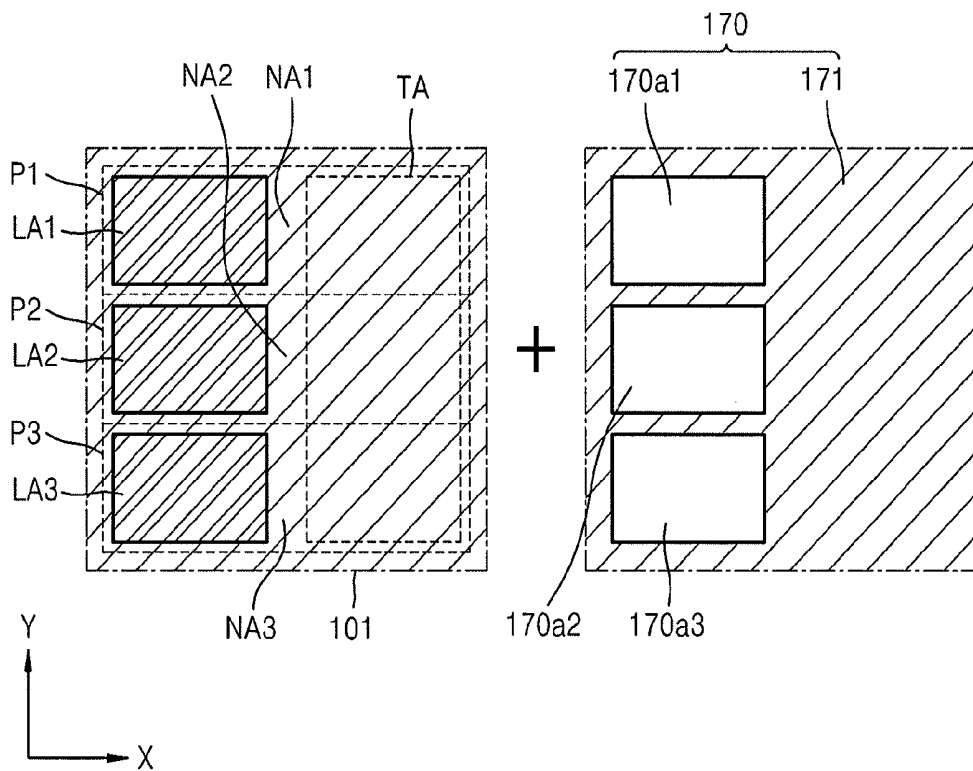


FIG. 5

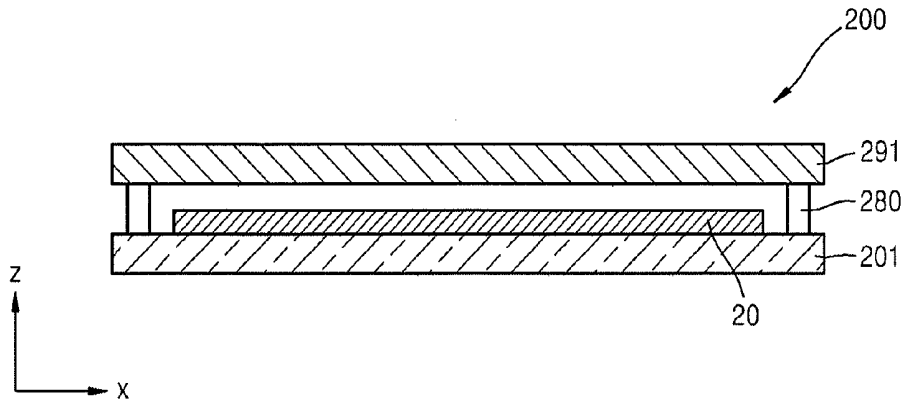


FIG. 6

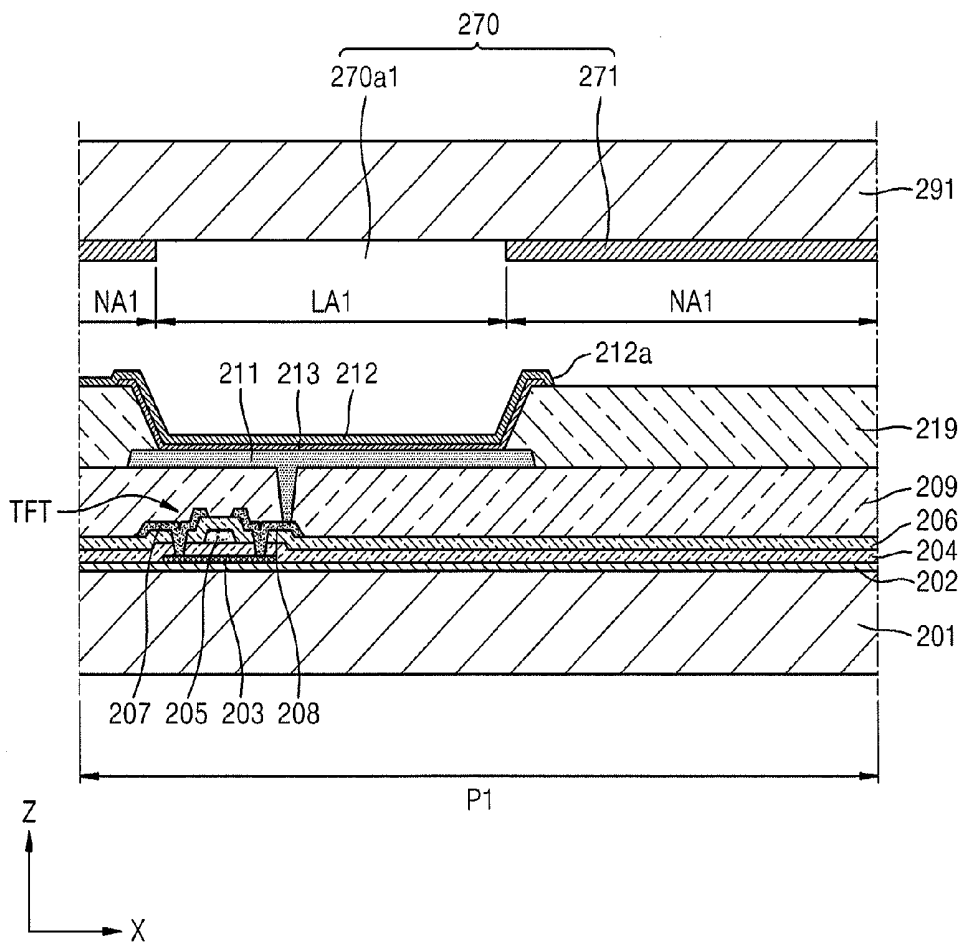


FIG. 7

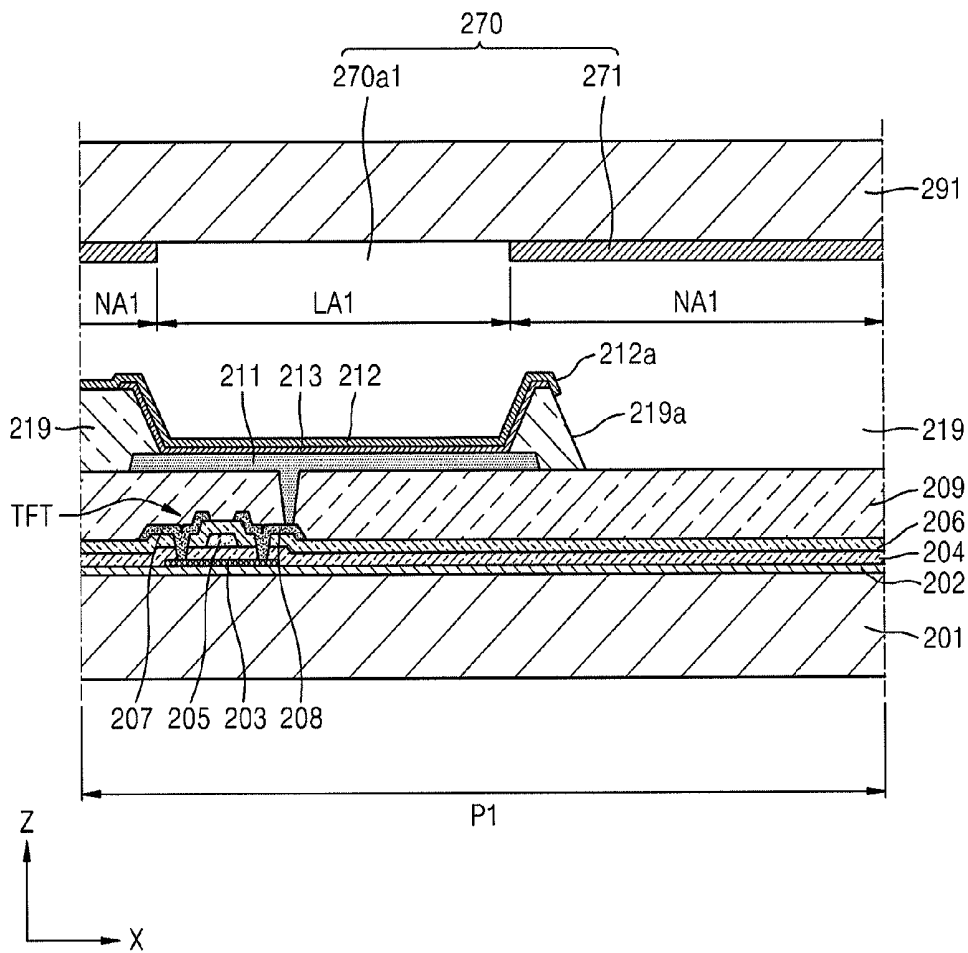


FIG. 8

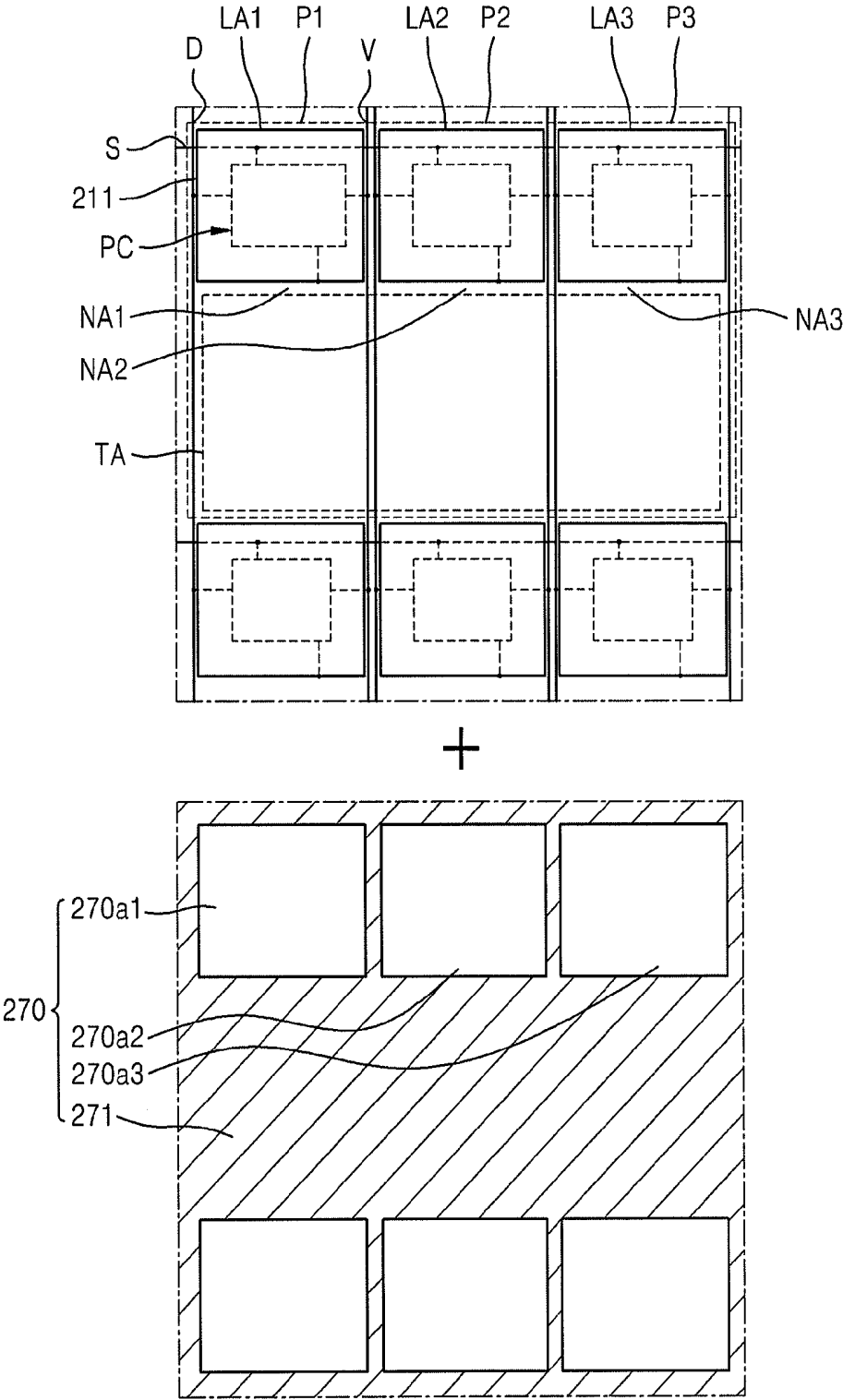


FIG. 9

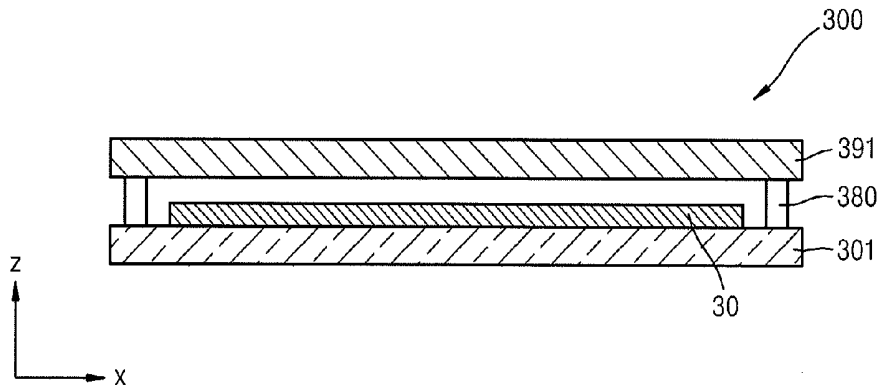


FIG. 10

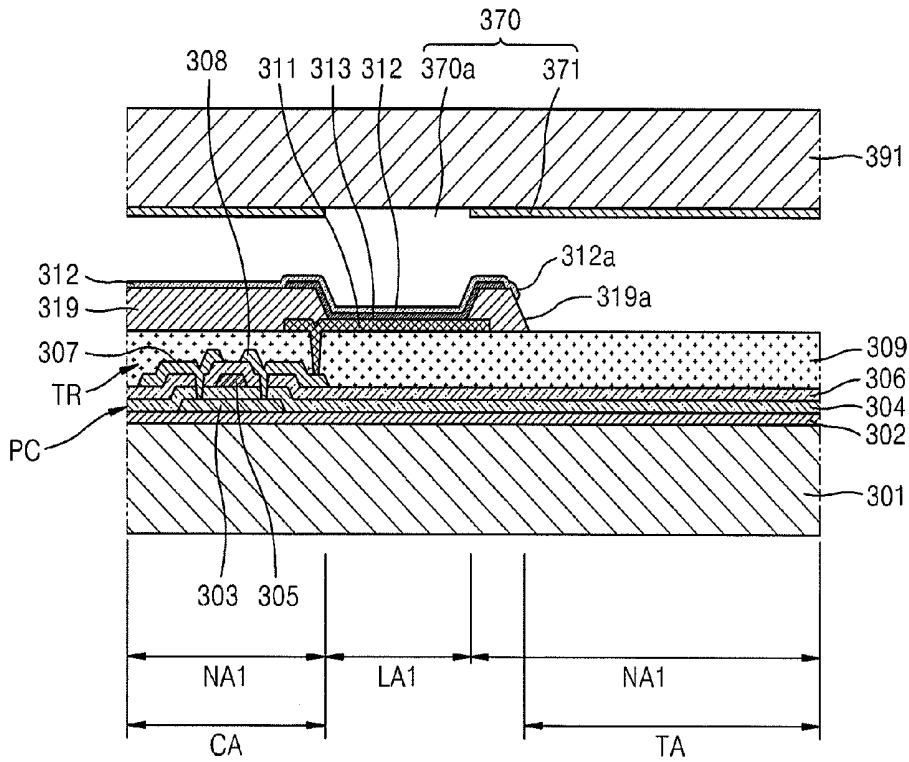
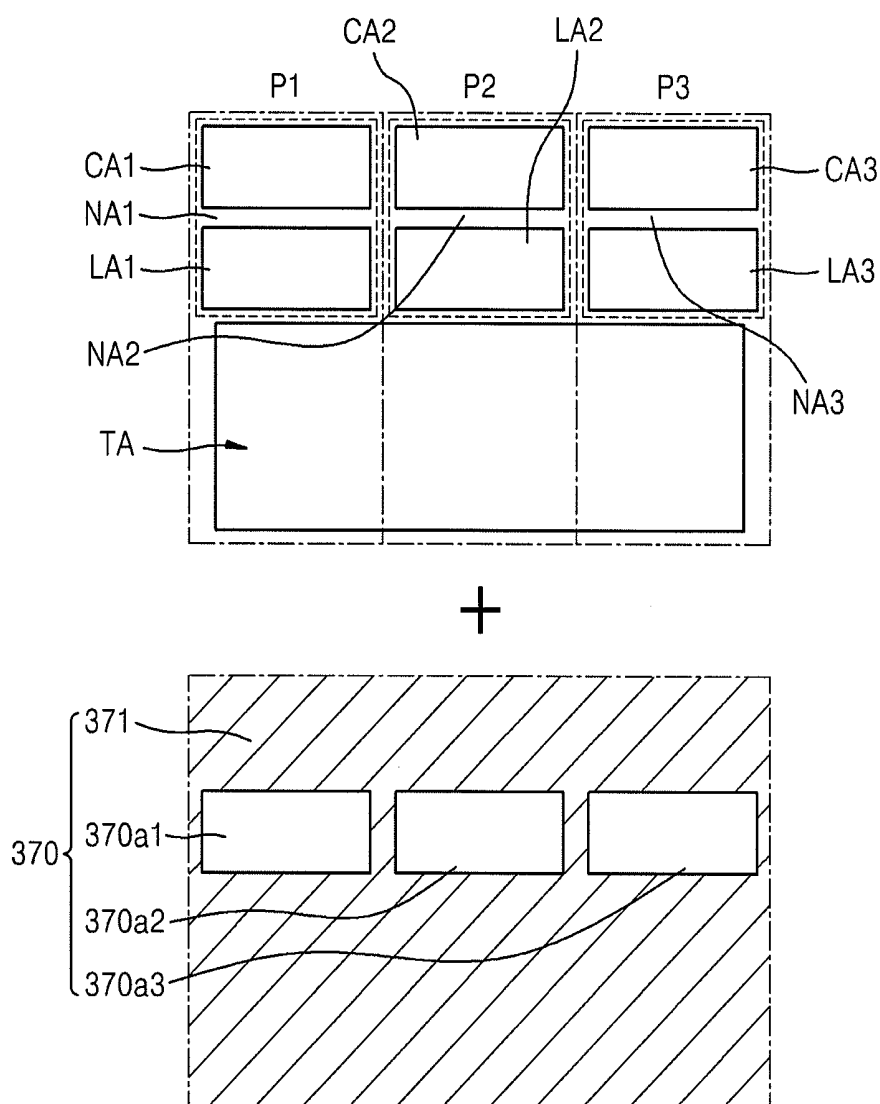


FIG. 11



**ORGANIC LIGHT EMITTING DISPLAY
APPARATUS****CROSS-REFERENCE TO RELATED PATENT
APPLICATION**

[0001] This application claims the benefit of Korean Patent Application No. 10-2013-0034688, filed on Mar. 29, 2013, in the Korean Intellectual Property Office, the disclosure of which is incorporated herein in its entirety by reference.

BACKGROUND

[0002] 1. Field

[0003] Example embodiments relate to an organic light emitting display apparatus, and more particularly, to an organic light emitting display apparatus capable of improving user convenience.

[0004] 2. Description of the Related Art

[0005] Recently, display apparatuses have been replaced with thin flat plate display apparatuses that may be portable. Among those flat plate display apparatuses, organic light emitting display apparatuses are self-emission type display apparatuses having wide viewing angle, high contrast, and fast response speed. Thus, the organic light emitting display apparatuses are considered as next generation display apparatuses.

[0006] A conventional organic light emitting display apparatus may include an intermediate layer, a first electrode, and a second electrode. The intermediate layer may include an organic emission layer, and when voltages are applied to the first and second electrodes, the organic emission layer emits light, e.g., visible rays.

SUMMARY

[0007] Example embodiments provide an organic light emitting display apparatus capable of easily improving user convenience.

[0008] According to an aspect of the example embodiments, there is provided an organic light emitting display apparatus including a substrate, an encapsulation member facing the substrate, a plurality of pixels between the substrate and the encapsulation member, each pixel including a light emission area and a non-emission area, a first electrode overlapping at least the light emission area, an intermediate layer on the first electrode and including an organic emission layer, a second electrode on the intermediate layer, and a reflective member on a bottom surface of the encapsulation member facing the substrate, and the reflective member including an opening corresponding to the light emission area, and a reflective surface around the opening and corresponding to the non-emission area.

[0009] The organic light emitting display apparatus may further include a transmission area formed on the non-emission area and disposed to overlap the reflective surface.

[0010] The transmission area may be formed commonly throughout at least two pixels among the plurality of pixels.

[0011] The second electrode may include a transmission window to correspond to the transmission area.

[0012] Each of the pixels may include at least one insulating layer, and the at least one insulating layer may include a transmission window to correspond to the transmission area.

[0013] Each of the pixels may include at least one insulating layer, the at least one insulating layer may include a

transmission window to correspond to the transmission area, the second electrode may include a transmission window to correspond to the transmission area, and the transmission window of the insulating layer and the transmission window of the second electrode may have the same patterns as each other.

[0014] The reflective surface of the reflective member may have a specular reflection property.

[0015] A reflectivity of the reflective member may be about 90% to 110% of an average reflectivity of the light emission area.

[0016] The reflectivity of the reflective surface of the reflective member with respect to light having a wavelength of about 700 nm to 800 nm may be greater than the reflectivity with respect to light having a wavelength of about 400 nm to 500 nm.

[0017] The reflective member may include Ni, Cr, W, V, or Mo.

[0018] Each of the pixels may include a pixel circuit unit for driving the light emission area, and the pixel circuit unit may be disposed to overlap the light emission area.

[0019] Each of the pixels may include a circuit area disposed on the non-emission area and a pixel circuit unit for driving the light emission area, wherein the pixel circuit unit may be disposed on the circuit area.

[0020] Each of the pixels may include a pixel circuit unit for driving the light emission area, and the pixel circuit unit may include a thin film transistor that is electrically connected to the first electrode and may include an active layer, a gate electrode, a source electrode, and a drain electrode.

BRIEF DESCRIPTION OF THE DRAWINGS

[0021] The above and other features and advantages of the example embodiments will become more apparent by describing in detail embodiments with reference to the attached drawings, in which:

[0022] FIG. 1 is a schematic cross-sectional view of an organic light emitting display apparatus according to an embodiment;

[0023] FIG. 2 is an enlarged view of portion A in FIG. 1;

[0024] FIG. 3 is a detailed cross-section of a light emission area in FIG. 2;

[0025] FIG. 4 is a detailed plan view of a reflective member from FIG. 1;

[0026] FIG. 5 is a schematic cross-sectional view of an organic light emitting display apparatus according to another embodiment;

[0027] FIG. 6 is a cross-sectional view of a pixel in the organic light emitting display apparatus of FIG. 5;

[0028] FIG. 7 is a cross-sectional view of a modified example of the pixel in FIG. 6;

[0029] FIG. 8 is a detailed plan view of a reflective member from FIG. 6;

[0030] FIG. 9 is a schematic cross-sectional view of an organic light emitting display apparatus according to another embodiment;

[0031] FIG. 10 is a cross-sectional view of a pixel in the organic light emitting display apparatus of FIG. 9; and

[0032] FIG. 11 is a detailed plan view of a reflective member from FIG. 10.

DETAILED DESCRIPTION

[0033] Hereinafter, embodiments will be described in detail with reference to accompanying drawings.

[0034] FIG. 1 is a schematic cross-sectional view of an organic light emitting display apparatus 100 according to an embodiment, and FIG. 3 is an enlarged view of portion A shown in FIG. 1. FIG. 3 is a diagram showing a light emission area shown in FIG. 2 in detail, and FIG. 4 is a plan view showing a reflective member of FIG. 1 in detail.

[0035] Referring to FIGS. 1 through 4, the organic light emitting display apparatus 100 may include a substrate 101, an encapsulation member 191, and a display unit 10 disposed between the substrate 101 and the encapsulation member 191. The substrate 101 and the encapsulation member 191 may be bonded to each other by a sealing member 180. A moisture absorbent or a filling material may be disposed in a space formed between the substrate 101 and the encapsulation member 191 by the sealing member 180.

[0036] The substrate 101 may be formed of a transparent glass material, e.g., containing mainly SiO₂. However, example embodiments are not limited thereto, e.g., the substrate 101 may be formed of a transparent plastic material. The encapsulation member 191 may be formed of the same material as that of the substrate 101, e.g., a transparent glass material or a plastic material.

[0037] The display unit 10 on the substrate 101 may include a plurality of pixels. Referring to FIG. 2, one pixel P1 is shown. Referring to FIG. 4, three pixels P1, P2, and P3 are shown.

[0038] Referring to FIG. 2, the pixel P1 includes a light-emission area LA1 and a non-emission area NA1. The light-emission area LA1 emits visible light, e.g., directly toward a user, to form images recognized by a user. The light-emission area LA1 may be formed in various shapes.

[0039] FIG. 3 is a diagram showing an example of the light-emission area LA1. Referring to FIG. 3, the light-emission area LA1 may include a first electrode 111, a second electrode 112, and an intermediate layer 113.

[0040] The first electrode 111 may include, e.g., indium tin oxide (ITO), indium zinc oxide (IZO), ZnO, and/or In₂O₃. Also, the first electrode 111 may include, e.g., Ag, Mg, Al, Pt, Pd, Au, Ni, Nd, Ir, Cr, Li, Yb, and/or Ca.

[0041] A buffer layer (not shown) may be formed before the first electrode 111 is formed on the substrate 101. The buffer layer (not shown) prevents impurity elements from penetrating into the substrate 101 while planarizing an upper surface of the substrate 101, and may be formed of various materials capable of performing the above functions. For example, the buffer layer (not shown) may be formed of an inorganic material, e.g., silicon oxide, silicon nitride, silicon oxynitride, aluminum oxide, aluminum nitride, titanium oxide, and/or titanium nitride, an organic material, e.g., polyimide, polyester, or acryl, or a stacked layer thereof.

[0042] The intermediate layer 113 is formed on the first electrode 111. The intermediate layer 113 includes an organic emission layer for emitting visible rays. The intermediate layer 113 may be formed as a low-molecular weight organic layer or a high-molecular weight organic layer. When the intermediate layer 113 is formed as a low-molecular weight organic layer, a single or multi-layer structure including a hole injection layer (HIL), a hole transport layer (HTL), an organic emission layer, an electron transport layer (ETL), and an electron injection layer (EIL) may be formed. The HIL may be formed of a phthalocyanine compound, e.g., copper

phthalocyanine, or a starburst type amine compound, e.g., TCTA, m-MTDATA, or m-MTDAPB. The HTL may be formed of, e.g., N,N'-bis(3-methylphenyl)-N,N'-diphenyl-[1,1'-biphenyl]-4,4'-diamine (TPD), N,N'-di(naphthalene-1-yl)-N,N'-diphenyl benzidine (α -NPD), and the like. The EIL may be formed of, e.g., LiF, NaCl, CsF, Li₂O, BaO, or Liq. The ETL may be formed of, e.g., Alq₃.

[0043] The organic emission layer may include a host material and a dopant material. The host material of the organic emission layer may be, e.g., Alq₃, 9,10-di(naphthyl-2-yl)anthracene (AND), 2-tert-butyl-9,10-bis-(β -naphthyl)-anthracene (TBADN), 4,4'-Bis(2,2-diphenylvinyl)-1,1'-biphenyl (DPVBi), 4,4'-Bis[2,2-di(4-methylphenyl)-ethen-1-yl]biphenyl (p-DMDPVBi), Tert(9,9-diarylfuorene)s (TDAF), 2-(9,9'-spirobifluorene-2-yl)-9,9'-spirobifluorene (BSDF), 2,7-bis(9,9'-spirobifluorene-2-yl)-9,9'-spirobifluorene (TSDF), Bis(9,9-diarylfuorene)s (BDAF), 4,4'-bis(2,2-diphenyl-ethene-1-yl)-4,4'-di-(tert-butyl)phenyl (p-TD-PVBi), N,N'-dicarbazolyl-3,5-benzene (mCP), 1,3,5-Tris(carbazol-9-yl)benzene (tCP), 4,4',4''-Tris(carbazol-9-yl)triphenylamine (TcTa), 4,4'-N,N'-dicarbazole-biphenyl (CBP), 4,4'-bis(9-carbazolyl)-2,2'-dimethyl-biphenyl (CBDP), 4,4'-Bis(carbazol-9-yl)-9,9-dimethylfluorene (DMFL-CBP), 4,4'-bis(carbazole-9-yl)-9,9-bis(9-phenyl-9H-carbazole)fluorene (FL-4CBP), 4,4'-bis(carbazol-9-yl)-9,9-ditolyfluorene (DPFL-CBP), or 9,9-bis(9-phenyl-9H-carbazol)fluorene (FL-2CBP). The dopant material of the organic emission layer may be, e.g., 1,4'-bis[4-(di-p-tolylamino)styryl]biphenyl (DPAVBi), 9,10-di-(2-naphthyl)anthracene (ADN), or 2-tert-butyl-9,10-di(naphth-2-yl)anthracene (TBADN).

[0044] The second electrode 112 may be formed on the intermediate layer 113. The second electrode 112 may be formed of a metal material, e.g., Ag, Mg, Al, Pt, Pd, Au, Ni, Nd, Ir, Cr, Li, or Ca. If necessary, the second electrode 112 may include, e.g., ITO, IZO, ZnO, or In₂O₃.

[0045] The non-emission area NA1 is formed around, e.g., around an entire perimeter of, the light emission area LA1 to be adjacent to the light emission area LA1. Circuits for driving the light emission area LA1 may be disposed on the non-emission area NA1. Also, as shown in FIGS. 2 and 4, the non-emission area NA1 may include a transmission area TA. The transmission area TA may be configured by forming a transmission window in one or more insulating layers (not shown) formed on the substrate 101. Otherwise, the transmission area TA may be configured by forming a transmission window in one or more conductive layers (not shown) formed on the substrate 101.

[0046] As shown in FIG. 4, each of the pixels P1, P2, and P3 includes a light emission area LA1, LA2, or LA3 and a non-emission area NA1, NA2, or NA3. Also, each of the pixels P1, P2, and P3 may include a common transmission area TA formed in the non-emission areas NA1, NA2, and NA3. However, example embodiments are not limited thereto, e.g., each of the pixels P1, P2, and P3 may include a separate transmission area TA separated from each other, like the light emission areas LA1, LA2, and LA3.

[0047] A reflective member 170 may be formed on, e.g., directly on, a surface of the encapsulation member 191. In particular, the reflective member 170 is formed on a surface of the encapsulation member 191, wherein the surface of the encapsulation member 191 faces the substrate 101. Referring to FIG. 2, the reflective member 170 includes at least one opening and a reflective surface 171. The reflective surface

171 is disposed around, e.g., peripherally with respect to, the at least one opening, e.g., around an entire perimeter of the opening **170a1**. Also, the reflective surface **171** corresponds to, e.g., completely overlaps, the non-emission area **NA1**, and the opening **170a1** corresponds to, e.g., completely overlaps, the light emission area **LA1**.

[0048] For example, referring to FIG. 4, the opening **170a1** of the reflective member **170** may correspond to the light emission area **LA1** of the pixel **P1**, an opening **170a2** may correspond to the light emission area **LA2** of the pixel **P2**, and an opening **170a3** may correspond to the light emission area **LA3** of the pixel **P3**. The reflective surface **171** of the reflective member **170** may be formed, e.g., continuously as a single layer, around the openings **170a1**, **170a2**, and **170a3** to correspond to the non-emission areas **NA1**, **NA2**, and **NA3** of the pixels **P1**, **P2**, and **P3**. That is, the reflective surface **171** overlaps the, e.g., entire, transmission area **TA**.

[0049] The reflective surface **171** exhibits reflectivity. In particular, the reflective surface **171** may exhibit a same or a similar reflectivity as that of each pixel **P1**, **P2**, or **P3**, i.e., reflectivity of the light emission areas **LA1**, **LA2**, or **LA3**. Since reflectivity of the light emission area **LA1**, **LA2**, or **LA3** is about 60%, the reflectivity of the reflective surface **171** is about 60%.

[0050] A difference between the reflectivity of the reflective surface **171** and an average reflectivity of the light emission areas **LA1**, **LA2**, and **LA3** may be about 10% or less. As such, the organic light emitting display apparatus **100** of the present embodiment may realize an image display function and a mirror function at the same time. For example, the reflectivity of the reflective surface **171** may be set to be similar to or the same as that of the light emission areas **LA1**, **LA2**, and **LA3** displaying images, e.g., about 90% to about 110% of the average reflectivity of the light emission areas **LA1**, **LA2**, and **LA3**. Therefore, a mirror function of the organic light emitting display apparatus **100** may be realized effectively without affecting the images displayed on the light emission areas **LA1**, **LA2**, and **LA3**.

[0051] In detail, the reflection type from the light emission areas **LA1**, **LA2**, and **LA3** is specular reflection, and the reflection type from the reflective surface **171** is also specular reflection. Thus, in the organic light emitting display apparatus **100**, diffuse reflection may be restrained and the specular reflection is increased in order to prevent blurring phenomenon. Thus, the mirror display function of the organic light emitting display apparatus **100** may be realized effectively.

[0052] To do this, the reflective surface **171** is formed by using a predetermined metal material, e.g., Ni, Cr, W, V, or Mo. Such predetermined metal material may exhibit reflectivity that is similar to that of the pixels **P1**, **P2**, and **P3**.

[0053] In detail, the reflectivity of the pixels **P1**, **P2**, and **P3** with respect to long wavelengths of light, e.g., about 700 nm to about 800 nm, is higher than the reflectivity of the pixels **P1**, **P2**, and **P3** with respect to short wavelengths of light, e.g., about 400 nm to about 500 nm. Thus, the reflectivity of the reflective surface **171** with respect to long wavelengths of light is set to be higher than the reflectivity of the reflective surface **171** with respect to the short wavelengths of light. As such, the reflection property of the reflective surface **171** may be similar to that of the light emission area **LA**.

[0054] Also, the reflective surface **171** has a predetermined thickness. In particular, the reflective surface **171** may have a thickness of about 500 μm or greater. If the thickness of the reflective surface **171** is less than 500 μm , light may be par-

tially transmitted through the reflective surface **171**, thereby reducing the reflectivity of the reflective surface **171** to a less than a desirable level, which in turn may make it difficult to effectively show the mirror display function of the organic light emitting display apparatus.

[0055] The organic light emitting display apparatus **100** of the present embodiment includes the reflective member **170** formed on a lower surface of the encapsulation member **191**. The reflective member **170** includes the openings **170a1**, **170a2**, and **170a3** corresponding to the light emission areas **LA1**, **LA2**, and **LA3** of the pixels **P1**, **P2**, and **P3** so as not to affect light emission, i.e., the display of images. Further, the reflective member **170** may include the reflective surface **171** around the openings **170a1**, **170a2**, and **170a3**, i.e., corresponding to the non-emission areas **NA1**, **NA2**, and **NA3**, so that the organic light emission display apparatus **100** may serve as a mirror display. Here, the reflectivity of the reflective surface **171** is set to be similar to that of the light emission areas **LA1**, **LA2**, and **LA3**, e.g., the reflectivity with respect to the light of longer wavelength (700 to 800 nm) is set to be higher than that with respect to the light of shorter wavelength (400 to 500 nm) so that the reflection type of the reflective surface **171** is similar to that of the light emission areas **LA1**, **LA2**, and **LA3**. Thus, the organic light emitting display apparatus **100** may exhibit uniform specular light reflection, e.g., from its entire surface overlapping all pixels, without degrading image quality characteristics.

[0056] Also, each of the pixels **P1**, **P2**, and **P3** selectively includes the transmission area **TA** in the non-emission area **NA1**, **NA2**, and/or **NA3**, so that the reflective surface **171** corresponds to the transmission area **TA**. Accordingly, the light reflected by the reflective surface **171** may be transmitted to the user effectively through the transmission area **TA**. Thus, the mirror display performance of the organic light emitting display apparatus **100** may be improved. Also, even when the light emission area **LA** of the organic light emitting display apparatus **100** stops operating, the light reflected by the reflective surface **171** may be transmitted to the user easily through the transmission area **TA**, and accordingly, the organic light emitting display apparatus **100** may serve as a general mirror.

[0057] FIG. 5 is a cross-sectional view schematically showing an organic light emitting display apparatus **200** according to another embodiment, and FIG. 6 is a cross-sectional view of a pixel **P1** in a display unit of the organic light emitting display apparatus **200** shown in FIG. 5. FIG. 7 shows another modified example of the pixel shown in FIG. 6, and FIG. 8 is a plan view showing a reflective member shown in FIG. 6. For convenience of description, differences relative to the previous embodiment will be described below.

[0058] Referring to FIGS. 5 through 8, the organic light emitting display apparatus **200** may include a substrate **201**, an encapsulation member **291**, and a display unit **20** disposed between the substrate **201** and the encapsulation member **291**. The substrate **201** and the encapsulation member **291** may be bonded to each other by a sealing member **280**.

[0059] The display unit **20** on the substrate **201** may include a plurality of pixels. Referring to FIG. 6, one pixel **P1** is shown. Referring to FIG. 8, three pixels **P1**, **P2**, and **P3** are shown.

[0060] Referring to FIG. 6, the pixel **P1** includes a light emission area **LA1** and a non-emission area **NA1**. The light emission area **LA1** emits visible light directly to realize images recognized by the user. In the light emission area **LA1**,

a first electrode **211**, a second electrode **212**, and an intermediate layer **213** are formed, e.g., an organic light emitting diode.

[0061] Also, as shown in FIG. 8, a pixel circuit unit PC may be disposed in the light emission area LA1. Referring to FIG. 8, a data line D, a scan line S, and a power line V may be connected to the pixel circuit unit PC. Also, the pixel circuit unit PC may include at least one thin film transistor TFT as shown in FIG. 6. In particular, the TFT is a driving transistor, and although not shown in FIG. 8, the pixel circuit unit PC may further include a switching transistor and a capacitor.

[0062] Referring to FIG. 6, a buffer layer **202** may be formed on the substrate **201**. As described above, since the buffer layer **202** is an optional element, it may be omitted.

[0063] The TFT is formed on the buffer layer **202**. The TFT may include an active layer **203**, a gate electrode **205**, a source electrode **207**, and a drain electrode **208**.

[0064] First, the active layer **203** having a predetermined pattern is formed on the buffer layer **202**. The active layer **203** may be formed of an inorganic semiconductor, e.g., amorphous silicon or polysilicon, oxide semiconductor, or organic semiconductor, and may include a source region, a drain region, and a channel region. The source and drain regions of the active layer **203** may be formed of amorphous silicon or crystalline silicon doped with group-III or group-V impurities.

[0065] A gate insulating layer **204** may be formed on the active layer **203**, and the gate electrode **205** may be formed on a predetermined region of the gate insulating layer **204**. The gate insulating layer **204** may be formed of an organic material or an inorganic material, e.g., SiNx or SiO₂, for insulating the active layer **203** from the gate electrode **205**.

[0066] The gate electrode **205** may include, e.g., Au, Ag, Cu, Ni, Pt, Pd, Al, or Mo, and an alloy, e.g., Al:Nd alloy or Mo:W alloy. However, example embodiments are not limited thereto. The gate electrode **205** may be formed to have a single-layered structure or a multi-layered structure.

[0067] An interlayer dielectric **206** may be formed on the gate electrode **205**. The interlayer dielectric **206** and the gate insulating layer **204** may be formed to expose the source region and the drain region of the active layer **203**, and the source electrode **207** and the drain electrode **208** may be formed to contact the exposed source and drain regions of the active layer **203**, respectively. The source electrode **207** and the drain electrode **208** may be formed of various conductive materials, and may have single-layered or multi-layered structures.

[0068] A passivation layer **209** may be formed on the TFT. In more detail, the passivation layer **209** may be formed on the source and drain electrodes **207** and **208**. The passivation layer **209** does not cover the entire portion of the drain electrode **208**, and may be configured to expose a predetermined region. The first electrode **211** may be formed to connect to the exposed drain electrode **208** through the passivation layer **209**.

[0069] The first electrode **211** may be formed, e.g., as an independent island type, in each of the pixels. A pixel defining layer **219** may be formed on the passivation layer **209** to cover edges of the first electrode **211**. The intermediate layer **213** may be formed on the first electrode **211**, and the intermediate layer **213** may include an organic emission layer to emit visible light. The second electrode **212** may be formed on the intermediate layer **213**.

[0070] The non-emission area NA1 may be formed around the light emission area LA1, e.g., around the organic light emitting diode, to be adjacent to the light emission area LA1. The non-emission area NA1 may include the transmission area TA. The transmission area TA may be configured by forming a transmission window **212a** in the second electrode **212**, e.g., the transmission window **212a** may expose an upper surface of the pixel defining layer **219**.

[0071] Also, as another embodiment, the transmission area TA may be configured by forming the transmission window **212a** in the second electrode **212** and a transmission window **219a** in the pixel defining layer **219**, as shown in FIG. 7. Here, the transmission window **212a** in the second electrode **212** may have the same pattern as that of the transmission window **219a** in the pixel defining layer **219**.

[0072] Although not shown in the drawings, the example embodiments are not limited thereto. That is, the transmission window may be formed in one or more insulating layers (not shown) or in one or more conductive layers (not shown) formed on the substrate **201**.

[0073] As shown in FIG. 8, each of the pixels P1, P2, and P3 includes the light emission area LA1, LA2, or LA3, respectively, and the pixels P1, P2, and P3 may include a common transmission area TA. However, example embodiments are not limited thereto, e.g., each of the pixels P1, P2, and P3 may include a separate transmission area TA, i.e., separate from each other like the light emission areas LA1, LA2, and LA3.

[0074] Referring back to FIG. 6, a reflective member **270** is formed on a surface of the encapsulation member **291**. In detail, the reflective layer **270** is formed on a surface of the encapsulation unit **291**, which faces the substrate **201**. The reflective layer **270** includes one or more openings **270a1**, and a reflective surface **271**. The reflective surface **271** is disposed around the openings **270a1**. Also, the reflective surface **271** is formed to correspond to the non-emission areas NA1, NA2, and NA3, and the openings **270a1** are formed to correspond to the light emission areas LA1, LA2, and LA3.

[0075] In more detail, referring to FIG. 8, the opening **270a1** of the reflective member **270** corresponds to the light emission area LA1 of the pixel P1, an opening **270a2** of the reflective member **270** corresponds to the light emission area LA2 of the pixel P2, and an opening **270a3** of the reflective member **270** corresponds to the light emission area LA3 of the pixel P3. The reflective surface **271** of the reflective member **270** is respectively formed on the non-emission areas NA1, NA2, and NA3 of the pixels P1, P2, and P3 around the openings **270a1**, **270a2**, and **270a3**. Thus, the reflective surface **271** overlaps the transmission areas TA of the non-emission areas NA1, NA2, and NA3.

[0076] The reflective surface **271** has an appropriate, i.e., a predetermined, reflectivity. In particular, the reflective surface **271** has a reflectivity that is the same as or similar to the reflectivity of the pixels P1, P2, and P3, i.e., the reflectivity of the light emission areas LA1, LA2, and LA3. Since the reflectivity of the light emission areas LA1, LA2, and LA3 is nearly 60%, the reflectivity of the reflective surface **271** is about 60%. Thus, a difference between the reflectivity of the reflective surface **271** and an average reflectivity of the light emission areas LA1, LA2, and LA3 may be about 10% or less.

[0077] As such, the organic light emitting display apparatus **200** of the present embodiment may serve as an image display apparatus and as a mirror at the same time. Here, the reflectivity of the reflective surface **271** is similar to or the same as that of the light emission areas LA1, LA2, and LA3 display-

ing images, e.g., is set to be about 90% to about 110% of the average reflectivity of the light emission areas LA1, LA2, and LA3. Therefore, a mirror function may be realized effectively without affecting the images displayed on the light emission areas LA1, LA2, and LA3.

[0078] In detail, the reflective surface 271 may be formed of a predetermined metal material, e.g., Ni, Cr, W, V, or Mo. Such materials may have a reflectivity that is similar to that of the pixels P1, P2, and P3. In particular, the reflectivity of the pixels P1, P2, and P3 with respect to light of long wavelength (700 to 800 nm) is higher than the reflectivity of the pixels P1, P2, and P3 with respect to light of short wavelength (400 to 500 nm). Thus, the reflectivity of the reflective surface 271 with respect to the light of long wavelength (700 to 800 nm) is set to be higher than that with respect to the light of short wavelength (400 to 500 nm).

[0079] Also, the reflective surface 271 has an appropriate, i.e., a predetermined, thickness. In particular, the reflective surface 271 may have a thickness of about 500 μm or greater. If the thickness of a reflective surface is less than 500 μm, partial light may transmit through the reflective surface, thereby reducing the reflectivity of the reflective surface. When light transmits through a reflective surface and reduces reflectivity, a mirror display function of the organic light emitting display apparatus may not be shown effectively.

[0080] Therefore, according to example embodiments, the organic light emitting display apparatus 200 of the present embodiment includes the reflective member 270 on a lower surface of the encapsulation member 291 and with a thickness of about 500 μm or greater. The reflective member 270 includes the openings 270a1, 270a2, and 270a3 respectively corresponding to the light emission areas LA1, LA2, and LA3 of the pixels P1, P2, and P3, so as not to affect the image display of the light emission areas LA1, LA2, and LA3. Further, the reflective member 270 includes the reflective surface 271 corresponding to the non-emission areas NA1, NA2, and NA3, so that the organic light emitting display apparatus 200 may function as a mirror display. Here, the reflectivity of the reflective surface 271 is set to be similar to that of the light emission areas LA1, LA2, and LA3, and in particular, the reflectivity with respect to the longer wavelength (700 to 800 nm) is set to be higher than that with respect to the shorter wavelength (400 to 500 nm) so that the reflection tendency is similar to that of the light emission areas LA1, LA2, and LA3. As such, the organic light emitting display apparatus 200 having uniform and specular reflection characteristic may be provided without degrading image quality characteristics.

[0081] Also, the pixel circuit unit PC including the TFT is disposed in the light emission area LA. Thus, in a case of a top emission type, i.e., when an image emitted from the light emission area LA is displayed toward the encapsulation member 290, the light emission area may be increased and an aperture ratio is increased, thereby improving the image quality.

[0082] Selectively, each of the pixels P1, P2, and P3 includes the transmission area TA in the non-emission area NA, and the reflective surface 271 corresponds to the transmission area TA. Then, the light reflected by the reflective surface 271 may be emitted effectively toward the user through the transmission area TA. Thus, when the image emitted from the light emission area LA of the organic light emitting display apparatus 200 is displayed toward the encapsulation member 290, the light reflected by the reflective

surface 271 is emitted toward the substrate 201 through the transmission area TA. Thus, at the substrate side 201, a general mirror function may be provided.

[0083] FIG. 9 is a schematic cross-sectional view of an organic light emitting display apparatus 300 according to another embodiment, FIG. 10 is a cross-sectional view showing a pixel in the organic light emitting display apparatus 300, and FIG. 11 is a plan view showing a reflective member in FIG. 10. For convenience of description, differences relative to the previous embodiments will be described below.

[0084] Referring to FIGS. 9 through 11, the organic light emitting display apparatus 300 may include a substrate 301, an encapsulation member 391, and a display unit 30 disposed between the substrate 301 and the encapsulation member 391. The substrate 301 and the encapsulation member 391 are bonded to each other by a sealing member 380.

[0085] The display unit 30 on the substrate 301 includes a plurality of pixels. FIG. 10 shows one pixel P1. FIG. 11 shows three pixels P1, P2, and P3.

[0086] Referring to FIG. 10, the pixel P1 includes a light emission area LA1 and a non-emission area NA1. The light emission area LA1 emits visible rays directly to display images recognized by the user. In the light emission area LA1, a first electrode 311, a second electrode 312, and an intermediate layer 313 are formed. In the non-emission area NA1, a circuit area CA1 and a transmission area TA are formed. The circuit area CA1 is disposed adjacent to the light emission area LA1, and as shown in FIG. 10, a pixel circuit unit PC may be disposed in the circuit area CA1.

[0087] The pixel circuit unit PC may include one or more TFT (TR). Although not shown in FIG. 10, data lines (not shown), scan lines (not shown), and power lines (not shown) may be connected to the pixel circuit unit PC, like in the previous embodiment.

[0088] Referring to FIG. 10, a buffer layer 302 may be formed on the substrate 301. As described above, since the buffer layer 302 is optional, it may be omitted.

[0089] A TFT TR may be formed on the buffer layer 302. The TFT TR may include an active layer 303, a gate electrode 305, a source electrode 307, and a drain electrode 308.

[0090] First, the active layer 303 having a predetermined pattern is formed on the buffer layer 302. A gate insulating layer 304 is formed on the active layer 303, and the gate electrode 305 is formed on a predetermined region on the gate insulating layer 304.

[0091] An interlayer dielectric 306 is formed on the gate electrode 305. The interlayer dielectric 306 and the gate insulating layer 304 are formed to expose the source region and the drain region of the active layer 303, and the source electrode 307 and the drain electrode 308 are formed to contact the exposed source and drain regions of the active layer 303, respectively.

[0092] A passivation layer 309 is formed on the TFT TR. In more detail, the passivation layer 309 is formed on the source and drain electrodes 307 and 308. The passivation layer 309 does not cover the entire portion of the drain electrode 308, and is configured to expose a predetermined region. The first electrode 311 is formed to connect to the exposed drain electrode 308.

[0093] The first electrode 311 may be formed as an independent island type in each of the pixels. A pixel defining layer 319 is formed on the passivation layer 309 to cover edges of the first electrode 311.

[0094] The intermediate layer 313 is formed on the first electrode 311, and the intermediate layer 313 includes an organic emission layer to emit visible light. The second electrode 312 is formed on the intermediate layer 313.

[0095] As described above, the non-emission area NA1 is formed adjacent to the light emission area LA1, and the non-emission area NA1 may include the circuit area CA1 and the transmission area TA.

[0096] The transmission area TA may be formed by forming a transmission window 312a in the second electrode 312 and a transmission window 319a in the pixel defining layer 319. Here, the transmission window 312a formed in the second electrode 312 may have a pattern that is the same as the transmission window 319a formed in the pixel defining layer 319.

[0097] Although not shown in FIG. 10, the example embodiments are not limited thereto. For example, the transmission window may be formed in only one of the second electrode 312 and the pixel defining layer 319. Also, the transmission window may be formed in one or more insulating layers (not shown) or in one or more conductive layers (not shown) formed on the substrate 301.

[0098] Meanwhile, as shown in FIG. 11, the pixels P1, P2, and P3 respectively include the light emission areas LA1, LA2, and LA3, and the circuit areas CA1, CA2, and CA3.

[0099] The pixels P1, P2, and P3 may include a common transmission area TA. However, the example embodiments are not limited thereto, e.g., the pixels P1, P2, and P3 may include separate transmission areas like the light emission areas LA1, LA2, and LA3.

[0100] A reflective member 370 is formed on a surface of the encapsulation member 391. In particular, the reflective member 370 is formed on the surface of the encapsulation member 391, which faces the substrate 301. The reflective member 370 includes one or more openings 370a1, 370a2, and 370a3, and a reflective surface 371. The reflective surface 371 is disposed around the openings 370a1, 370a2, and 370a3. Also, the reflective surface 371 is formed to correspond to the non-emission area NA, and the openings 370a1, 370a2, and 370a3 are formed to correspond to the light emission areas LA1, LA2, and LA3.

[0101] In particular, referring to FIG. 11, the opening 370a1 of the reflective member 370 corresponds to the light emission area LA1 of the pixel P1, the opening 370a2 corresponds to the light emission area LA2 of the pixel P2, and the opening 370a3 corresponds to the light emission area LA3 of the pixel P3. The reflective surface 371 of the reflective member 370 is formed on the non-emission areas NA1, NA2, and NA3 of the pixels P1, P2, and P2, around the openings 370a1, 370a2, and 370a3. Therefore, the reflective surface 371 also overlaps the circuit areas CA1, CA2, and CA3 and the transmission area TA of the non-emission areas NA1, NA2, and NA3.

[0102] The reflective surface 371 has an appropriate reflectivity. In particular, the reflective surface 371 has the reflectivity that is the same as or similar to that of the pixels P1, P2, and P3, and in particular, the reflectivity of the light emission areas LA1, LA2, and LA3. Since the reflectivity of the light emission areas LA1, LA2, and LA3 is nearly 60%, the reflectivity of the reflective surface 371 is about 60%.

[0103] Roughly a difference between the reflectivity of the reflective surface 371a and an average reflectivity of the light emission areas LA1, LA2, and LA3 may be about 10% or less. As such, the organic light emitting display apparatus 300

of the present embodiment may provide both an image display function and a mirror function, at the same time. In other words, the organic light emitting display apparatus 300 of the present embodiment may provide an image display function through the light emission areas, i.e., where the organic light emitting diode emits light, and a mirror function through the non-transmission areas, i.e., through areas surrounding the transmission areas. Here, the reflectivity of the reflective surface 371 is the same as or similar to that of the light emission areas LA1, LA2, and LA3, i.e., the reflectivity of the reflective surface 371 is set as about 90% to about 110% of the average reflectivity of the light emission areas LA1, LA2, and LA3, so that the mirror function may be served effectively without affecting the image quality of the images emitted from the light emission areas LA1, LA2, and LA3.

[0104] The reflective surface 371 is formed by using a predetermined metal material, e.g., Ni, Cr, W, V, or Mo. Such metal materials have reflectivity that is similar to that of the pixels P1, P2, and P3. In particular, the reflectivity of the pixels P1, P2, and P3 with respect to light of long wavelength (700 to 800 nm) is higher than the reflectivity of the pixels P1, P2, and P3 with respect to light of short wavelength (400 to 500 nm). Thus, the reflectivity of the reflective surface 371 with respect to the light of long wavelength (700 to 800 nm) is set to be higher than that with respect to the light of short wavelength (400 to 500 nm). As such, the reflection property of the reflective surface 371 may be similar to that of the light emission area LA.

[0105] Also, the reflective surface 371 has an appropriate thickness. In particular, the reflective surface 371 may have a thickness of 500 μm or greater. If the thickness of the reflective surface 371 is less than 500 μm , partial light transmits through the reflective surface 371, thereby reducing the reflectivity of the reflective surface 371 less than a desired level. Thus, it is difficult to show the mirror display function of the organic light emitting display apparatus 300 effectively.

[0106] The organic light emitting display apparatus 300 of the present embodiment includes the reflective member 370 formed on a lower surface of the encapsulation member 391. The reflective member 370 includes openings 370a1 corresponding to the light emission areas LA of the pixels P1, P2, and P3 so as not to affect the display of images, and includes the reflective surface 371 corresponding to the non-emission areas NA1, NA2, and NA3 of the pixels P1, P2, and P3 so that the organic light emission display apparatus 300 may serve as a mirror display. Here, the reflectivity of the reflective surface 371 is set to be similar to that of the light emission areas LA1, LA2, and LA3, and in particular, the reflectivity with respect to the light of longer wavelength (700 to 800 nm) is set to be higher than that with respect to the light of shorter wavelength (400 to 500 nm) so that the reflection type of the reflective surface 371 is similar to that of the light emission areas LA1, LA2, and LA3. Thus, the organic light emitting display apparatus 300 that is uniform and shows the specular reflection property may be provided without degrading the image quality characteristics.

[0107] Also, the pixel circuit unit PC including the TFT TR is disposed on the circuit area CA of the non-emission area NA that does not overlap the light emission area LA. Thus, in a case of a bottom emission type in which the images emitted from the light emission area LA are displayed toward the substrate 301, the light emitted from the light emission area

LA may proceed without interruption of the pixel circuit unit PC, thereby improving image quality.

[0108] Alternately, the pixels P1, P2, and P3 include the transmission area TA in the non-emission areas NA and the reflective surface 371 corresponds to the transmission area TA. Thus, the light reflected by the reflective surface 371 may be discharged to the user effectively through the transmission area TA. As such, in a case where the image emitted from the light emission area LA of the organic light emitting display apparatus 300 is displayed toward the substrate 301, the light reflected by the reflective surface 371 is discharged easily through the transmission area TA to the user, thereby improving the mirror display performance of the organic light emitting display apparatus 300.

[0109] As described above, according to the organic light emitting display apparatus of the example embodiments, user convenience may be improved easily. In contrast, when the first electrode, the second electrode, and other metal layers in the conventional organic light emitting display apparatus reflect external light, which reduces display characteristics, e.g., visibility of a user, an image quality of the organic light emitting display apparatus may decrease. Also, reflective characteristics of the first electrode, the second electrode, and metal layers in the light emission area may be very different from reflective characteristics in portions peripheral to the light emission area, so there is a limitation in increasing image quality and convenience of a user of the organic light emitting display apparatus.

[0110] While the example embodiments has been particularly shown and described with reference to exemplary embodiments thereof, it will be understood by those of ordinary skill in the art that various changes in form and details may be made therein without departing from the spirit and scope of the example embodiments as defined by the following claims.

What is claimed is:

1. An organic light emitting display apparatus, comprising:
 - a substrate;
 - an encapsulation member facing the substrate;
 - a plurality of pixels between the substrate and the encapsulation member, each pixel including a light emission area and a non-emission area;
 - a first electrode overlapping at least the light emission area;
 - an intermediate layer on the first electrode and including an organic emission layer;
 - a second electrode on the intermediate layer; and
 - a reflective member on a bottom surface of the encapsulation member, the bottom surface of the encapsulation member facing the substrate, and the reflective member including:

an opening corresponding to the light emission area, and a reflective surface around the opening and corresponding to the non-emission area.

2. The organic light emitting display apparatus of claim 1, further comprising a transmission area on the non-emission area, the transmission area overlapping the reflective surface of the reflective member.

3. The organic light emitting display apparatus of claim 2, wherein the transmission area is common to at least two pixels among the plurality of pixels.

4. The organic light emitting display apparatus of claim 2, wherein the second electrode includes a transmission window corresponding to the transmission area.

5. The organic light emitting display apparatus of claim 2, wherein each of the pixels includes at least one insulating layer, the at least one insulating layer including a transmission window corresponding to the transmission area.

6. The organic light emitting display apparatus of claim 5, wherein the second electrode includes a transmission window corresponding to the transmission area, the transmission window of the insulating layer and the transmission window of the second electrode have same patterns.

7. The organic light emitting display apparatus of claim 1, wherein the reflective surface of the reflective member exhibits a specular reflection property.

8. The organic light emitting display apparatus of claim 1, wherein a reflectivity of the reflective member is about 90% to about 110% of an average reflectivity of the light emission area.

9. The organic light emitting display apparatus of claim 1, wherein the reflectivity of the reflective surface of the reflective member with respect to light having a wavelength of about 700 nm to 800 nm is greater than the reflectivity with respect to light having a wavelength of about 400 nm to 500 nm.

10. The organic light emitting display apparatus of claim 1, wherein the reflective member includes at least one of Ni, Cr, W, V, and Mo.

11. The organic light emitting display apparatus of claim 1, wherein each of the pixels includes a pixel circuit unit configured to drive the light emission area, the pixel circuit unit overlapping the light emission area.

12. The organic light emitting display apparatus of claim 1, wherein each of the pixels includes a circuit area on the non-emission area and a pixel circuit unit for driving the light emission area, the pixel circuit unit being on the circuit area.

13. The organic light emitting display apparatus of claim 1, wherein each of the pixels includes a pixel circuit unit for driving the light emission area, and the pixel circuit unit includes a thin film transistor electrically connected to the first electrode and includes an active layer, a gate electrode, a source electrode, and a drain electrode.

* * * * *

专利名称(译)	有机发光显示装置		
公开(公告)号	US20140291637A1	公开(公告)日	2014-10-02
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[标]申请(专利权)人(译)	三星显示有限公司		
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摘要(译)

一种有机发光显示装置，包括基板，面向基板的封装构件，基板与封装构件之间的多个像素，每个像素包括发光区域和非发光区域，第一电极至少重叠发光区域，第一电极上的中间层，包括有机发光层，中间层上的第二电极，以及封装构件的底表面上的反射构件，封装构件的底表面面向基板，反射构件包括对应于发光区域的开口，以及围绕开口并对应于非发射区域的反射表面。

